## WHAT IS CLAIMED IS:

- 1. A method of making a free-standing, internally-supported, three-dimensional object, the outer surface of the object comprising a plurality of intersecting facets, at least a sub-set of said intersecting facets having a diamond layer of substantially uniform depth, said method comprising the steps of:
- (a) providing a mold having an exposed surface defining the sub-set of intersecting facets;
- (b) growing a diamond layer of substantially uniform depth over the exposed surface;
  - (c) depositing a backing layer over at least a portion of the diamond layer; and
- (d) removing the mold to expose the surface of the diamond layer grown immediately contiguous to the mold.
- 2. The method of Claim 1 wherein the mold is a silicon substrate fabricated to define the sub-set of intersecting facets.
  - 3. The method of Claim 2 wherein the mold is removed by chemical etching.
- 4. The method of Claim 1 further including the step of pretreating the exposed surface of the mold to enhance the growth of the diamond layer.
- 5. The method of Claim 4 wherein carbon atoms are deposited on the exposed surface of the mold to enhance the growth of the diamond layer.
- 6. The method of Claim 5 wherein the carbon atoms are deposited on the exposed surface of the mold by exposing the surface to a carbon containing plasma.

- 7. The method of Claim 1 wherein the sub-set of intersecting facets includes planar facets.
- 8. The method of Claim 1 wherein the sub-set of intersecting facets includes non-planar facets.
- 9. A method of fabricating a free-standing object comprising a three-dimensional structure covered by a diamond film having an exposed surface, said method comprising the steps of:

growing a diamond film on a preselected exposed surface of a substrate;

providing a backing on at least a portion of the grown diamond film; and

removing the substrate to expose the diamond surface defined by the preselected

surface of the substrate on which the diamond was grown.

- 10. The method of Claim 9 wherein the substrate is silicon.
- 11. The method of Claim 9 including the further step of pretreating the preselected exposed surface to enhance the growth of diamond thereon.
- 12. The method of Claim 11 wherein a carbon seed layer is formed on the preselected exposed surface of the substrate.
- 13. The method of Claim 9 wherein the preselected surface of the substrate includes the intersection of two facets.
- 14. A method of fabricating a free-standing, internally-supported, three-dimensional object, the outer surface of the object comprising a plurality of intersecting facets, at least a sub-set of said intersecting facets having an exposed diamond surface, said method comprising the steps of:

growing a diamond film on a preselected exposed surface of a substrate;

providing a backing layer covering at least a portion of the grown diamond film;

and

removing the substrate so that the exposed diamond surface is the surface grown immediately contiguous to the substrate.

- 15. The method of Claim 14 wherein the substrate is silicon.
- 16. The method of Claim 15 wherein the substrate is removed by chemical etching.
- 17. The method of Claim 14 wherein the backing layer covers the entire diamond film.
- 18. The method of Claim 14 wherein the backing layer is electrically conducting.
- 19. The method of Claim 14 wherein the backing layer is electrically non-conducting.
  - 20. The method of Claim 19 wherein the backing layer is epoxy.
- 21. The method of Claim 14 including the further step of forming a carbon seed layer on the preselected exposed surface of the substrate to facilitate the growth of the diamond film thereon.
- 22. The method of Claim 21 wherein the diamond seed layer is formed by exposing the preselected exposed surface of the substrate to a carbon containing activated gas.

23. The method of Claim 22 wherein the diamond seed layer is formed by: grounding the substrate;

providing ionized carbon atoms; and

exposing the preselected exposed surface of the substrate to the ionized carbon atoms.

- 24. The method of Claim 22 wherein the activated gas is a plasma.
- 25. The method of Claim 24 wherein the plasma is formed by energizing a mixture of hydrogen and hydrocarbon gases.
- 26. The method of Claim 22 wherein the diamond seed layer is formed by chemical vapor deposition.
- 27. The method of Claim 14 wherein the diamond is grown by chemical vapor deposition.
- 28. The method of Claim 14 wherein the intersecting facets include planar facets.
- 29. The method of Claim 14 wherein the intersecting facets include non-planar facets.
- 30. The method of Claim 14 wherein the exposed diamond surface forms the surface of a waveguide.
- 31. The method of Claim 14 wherein the object is a bi-polar plate for a fuel cell.
- 32. A method of making a free-standing, internally-supported, threedimensional object, the outer surface of the object comprising a plurality of intersecting

facets, at least a sub-set of said intersecting facets having a diamond layer of substantially uniform depth, said method comprising the steps of:

- (a) fabricating a silicon substrate to provide a molding surface defining the sub-set of intersecting facets;
  - (b) seeding the molding surface of the substrate with carbon;
- (c) growing a diamond layer of substantially uniform depth over the molding surface of the substrate;
  - (d) forming an internally-supporting backing layer over the diamond layer; and
- (e) chemically etching the substrate to expose the surface of the diamond layer grown contiguous to the molding surface of the substrate.
- 33. The method of Claim 32 wherein molding surface is seeded by chemical vapor deposition.
- 34. The method of Claim 32 wherein the diamond layer is grown by chemical vapor deposition.